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**IN THE CLAIMS**

Please cancel claims 1, 2, 17 and 18, and amend the remaining claims to read as indicated below.

1. (canceled)

2. (canceled)

3. (currently amended) ~~The illumination system according to claim 2, An~~
illumination system for lithography with wavelengths of ≤ 193 nm comprising:

- (a) a first optical element, which is divided into first raster elements and lies in a first plane,
wherein said first plane defines an x-direction and a y-direction,
wherein said first raster elements each have an x-direction and a y-direction with an aspect ratio, and
wherein at least two of said first raster elements have aspect ratios of different magnitude; and
- (b) a second optical element, which is divided into second raster elements, wherein a second raster element is assigned to a first raster element,
wherein the illumination system defines a field,
wherein said field is illuminated in an object plane of the illumination system, and
wherein at least some of said second raster elements have an anamorphic optical effect, which is selected such that an aspect ratio of images of said first raster elements is substantially the same in said object plane, independent of said aspect ratio of said first raster elements.

4. (currently amended) The illumination system according to claim ~~4~~ 3, wherein at least one of said at least two first raster elements with aspect ratios of different magnitude has an anamorphic optical effect.

5. (currently amended) The illumination system according to claim-~~1~~3, wherein said at least two first raster elements with aspect ratios of different magnitude have an isotropic optical effect.

6. (previously presented) The illumination system according to claim 5, wherein said first raster elements have an isotropic optical effect.

7. (currently amended) The illumination system according to claim-~~1~~4, wherein said first raster elements that have an anamorphic optical effect are of a shape selected from the group consisting of cylinders and toroids.

8. (currently amended) The illumination system according to claim-~~2~~3, wherein said second raster elements ~~that have~~ element that has an anamorphic optical effect ~~are~~ is of a shape selected from the group consisting of cylinders and toroids.

9. (currently amended) ~~The illumination system according to claim 1, An~~
illumination system for lithography with wavelengths of ≤ 193 nm comprising:
a first optical element, which is divided into first raster elements and lies in a first
plane,
wherein said first plane defines an x-direction and a y-direction,
wherein said first raster elements each have an x-direction and a y-direction with an
aspect ratio,
wherein at least two of said first raster elements have aspect ratios of different
magnitude, and
wherein all of said first raster elements are completely illuminated in said first plane.

10. (currently amended) The illumination system according to claim-~~1~~9, further comprising a collector unit, which illuminates said first plane with said first raster elements.

11. (currently amended) The illumination system according to claim-1 9, further comprising at least one field mirror.

12. (currently amended) The illumination system according to claim-2 3, further comprising at least one field mirror, wherein said second raster elements and said at least one field mirror image said assigned first raster elements in an object plane of the illumination system.

13. (currently amended) The illumination system according to claim-1 9, wherein said first raster elements are rectangular.

14. (currently amended) ~~The illumination system according to claim 1, An~~
illumination system for lithography with wavelengths of ≤ 193 nm comprising:
a first optical element, which is divided into first raster elements and lies in a first plane,
wherein said first plane defines an x-direction and a y-direction,
wherein said first raster elements each have an x-direction and a y-direction with an aspect ratio,
wherein at least two of said first raster elements have aspect ratios of different magnitude,
wherein the illumination system defines a field to be illuminated in an object plane of the illumination system, and
wherein said field represents a segment of a ring field.

15. (currently amended) A projection exposure system for microlithography, comprising:

~~an illumination system according to claim 1 with~~

(a) an illumination system for lithography with wavelengths of ≤ 193 nm having:

a first optical element, which is divided into first raster elements and lies in a first plane,

wherein said first plane defines an x-direction and a y-direction,

wherein said first raster elements each have an x-direction and a y-direction with an aspect ratio, and wherein at least two of said first raster elements have aspect ratios of different magnitude;

- (b) an exit pupil, which partially collects an emission produced by a light source and further guides it to illuminate a field in an object plane of the illumination system;
- (c) a pattern-bearing mask, which lies in said object plane;
- (d) a projection device, with an entrance pupil, which coincides with an exit pupil of the illumination system, wherein said projection device images a lighted portion of said pattern-bearing mask in an image field of said projection device; and
- (e) a light-sensitive substrate, which lies in a plane of said image field.

16. (previously presented) A method for producing microelectronic components, comprising using the projection exposure system according to claim 15.

17. (canceled)

18. (canceled)

Please add the following claims, newly numbered as claims 19 through 23.

19. (new) The illumination system according to claim 9, further comprising: a second optical element, which is divided into second raster elements, wherein a second raster element is assigned to a first raster element, and wherein at least one second raster element has an anamorphic optical effect.

20. (new) An illumination system, comprising:
an optical element having a first raster element and a second raster element,
wherein said first raster element has a first aspect ratio,

wherein said second raster element has a second aspect ratio,
wherein said first aspect ratio is not equal to said second aspect ratio,
wherein the illumination system defines a field to be illuminated in an object plane
of the illumination system, and
wherein said field represents a segment of a ring field.

21. (new) An illumination system for radiation wavelengths of ≤ 193 nm,
comprising:

an optical element having a first raster element and a second raster element of
different sizes,
wherein the illumination system defines a field to be illuminated in an object plane
of the illumination system, and
wherein said field represents a segment of a ring field.

22. (new) An illumination system, comprising:

an optical element having a first raster element and a second raster element,
wherein said first raster element has a first aspect ratio,
wherein said second raster element has a second aspect ratio,
wherein said first aspect ratio is not equal to said second aspect ratio, and
wherein said first raster element is completely illuminated in a plane.

23. (new) An illumination system for radiation wavelengths of ≤ 193 nm,
comprising:

an optical element having a first raster element and a second raster element of
different sizes,
wherein said first raster element is completely illuminated in a plane.